



				U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. MI22-2347	PRIORITY SERIAL NO. 10/039,456	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Ying Huang et al.			
				FILING DATE	GROUP		
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*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
JN	AA	5,946,601	8/99	Wong et al.			
	AB	6,033,979	3/00	Endo			
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		Document Number	Date	Country	Class	Subclass	Translation
							Yes
							No
	AM						
	AN						
	AO						
	AP						
	AQ						
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JN	AR		Ballga, John, "Options for CVD of Dielectrics Include Low-k Materials," Semiconductor International June 1998, pp. 1-6				
	AS		Singer, Peter, "Dual-Damascene Challenges Dielectric-Etch," Semiconductor International August 1999, pp. 1-5				
	AT						
EXAMINER	JOSEPH NGUYEN			DATE CONSIDERED		9/21/04	
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

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